

Montréal, Québec, Canada
August 22-27, 2010

Conference topics

Nanostructure synthesis and modification
Ion-driven self-organization, nanopatterning
Defect-induced modification of materials
Ultra-low energy implantation
Focused ion beam, ion lithography
Cluster ions, single ions, swift heavy ions, highly-charged ions
Plasma immersion, plasma-induced modification/etching
Modification of semiconductors, metals and ceramics
Application to electronic, magnetic and optical materials
Irradiation effects in insulators and nuclear materials
Modification of polymers and biomaterials

17th International conference on ion beam modification of materials

Local Organization

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E. Saint-Jacques (RQMP), G. Ross (INRS-ÉMT)

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